

## **Fabrication of S/CoS<sub>2</sub>/NiS<sub>2</sub>/PZH composite using hydrothermal technology for high-performance supercapacitors**

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**Table S1** The equivalent internal resistance ( $R_s$ ) and the charge-transfer resistance ( $R_{ct}$ ) of PZH, S/CoS<sub>2</sub>/NiS<sub>2</sub>, S/CoS<sub>2</sub>/NiS<sub>2</sub>/PZH-30.

| Sample                                       | $R_{ct}$ ( $\Omega$ ) | $R_s$ ( $\Omega$ ) |
|--|-----------------------|--------------------|
| PZH  | 1.620                 | 0.7093             |
| S/CoS <sub>2</sub> /NiS <sub>2</sub>         | 1.259                 | 0.7051             |
| S/CoS <sub>2</sub> /NiS <sub>2</sub> /PZH-30 | 0.408                 | 0.695              |